### **Power**

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### **Outline**

- Power
  - Power & Energy
  - Dynamic Power
  - Static Power (Leakage Power)
  - Low Power Design Technologies

## **Power and Energy**

- □ Power is drawn from a voltage source attached to the V<sub>DD</sub> pin(s) of a chip.
- ☐ Instantaneous Power: P(t) =
- $\Box$  Energy: E =
- $\Box$  Average Power:  $P_{\text{avg}} =$

## **Power in Circuit Elements**

$$P_{VDD}(t) = I_{DD}(t)V_{DD}$$

$$P_{R}(t) = \frac{V_{R}^{2}(t)}{R} = I_{R}^{2}(t)R$$

$$E_C = \int_0^\infty I(t)V(t)dt = \int_0^\infty C\frac{dV}{dt}V(t)dt$$
$$= C\int_0^{V_C} V(t)dV = \frac{1}{2}CV_C^2$$

$$\stackrel{+}{V_C} \stackrel{+}{=} C \stackrel{\downarrow}{\downarrow} I_C = C \frac{dV}{dt}$$

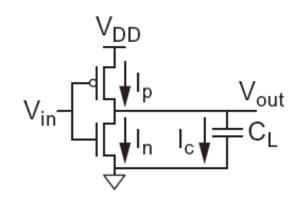
# **Charging a Capacitor**

- When the gate output rises
  - Energy stored in capacitor is

$$E_C = \frac{1}{2} C_L V_{DD}^2$$

But energy drawn from the supply is

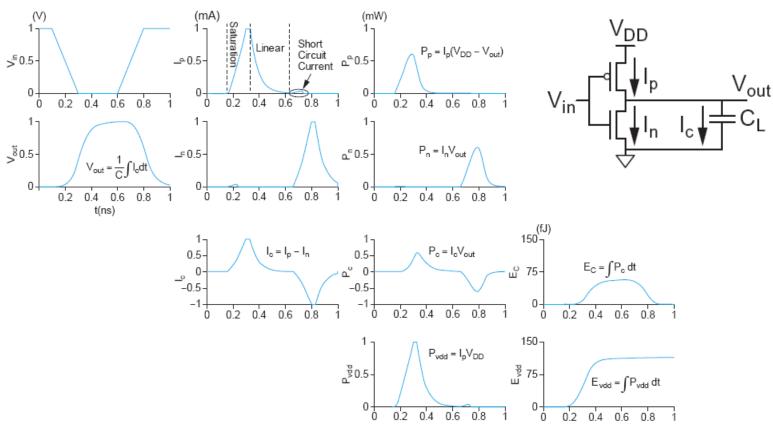
$$E_{VDD} = \int_{0}^{\infty} I(t)V_{DD}dt = \int_{0}^{\infty} C_{L} \frac{dV}{dt} V_{DD}dt$$
$$= C_{L}V_{DD} \int_{0}^{V_{DD}} dV = C_{L}V_{DD}^{2}$$



- Half the energy from V<sub>DD</sub> is dissipated in the pMOS transistor as heat, other half stored in capacitor
- When the gate output falls
  - Energy in capacitor is dumped to GND
  - Dissipated as heat in the nMOS transistor

## **Switching Waveforms**

 $\Box$  Example:  $V_{DD} = 1.0 \text{ V}$ ,  $C_L = 150 \text{ fF}$ , f = 1 GHz



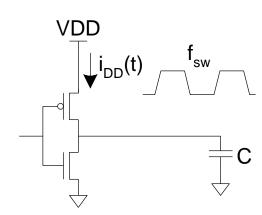
## **Switching Power**

$$P_{\text{switching}} = \frac{1}{T} \int_{0}^{T} i_{DD}(t) V_{DD} dt$$

$$= \frac{V_{DD}}{T} \int_{0}^{T} i_{DD}(t) dt$$

$$= \frac{V_{DD}}{T} \left[ Tf_{\text{sw}} CV_{DD} \right]$$

$$= CV_{DD}^{2} f_{\text{sw}}$$



## **Activity Factor**

- $\Box$  Suppose the system clock frequency = f
- $\Box$  Let  $f_{sw} = \alpha f$ , where  $\alpha =$  activity factor
  - If the signal is a clock,  $\alpha = 1$
  - If the signal switches once per cycle,  $\alpha = \frac{1}{2}$
- Dynamic power:

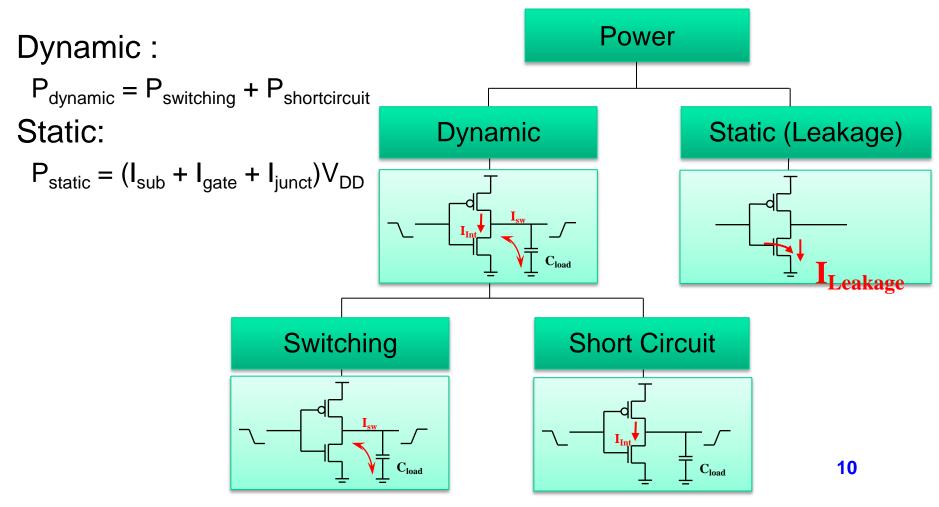
$$P_{\text{switching}} = \alpha C V_{DD}^2 f$$

### **Short Circuit Current**

- When transistors switch, both nMOS and pMOS networks may be momentarily ON at once
- Leads to a blip of "short circuit" current.
- < 10% of dynamic power if rise/fall times are comparable for input and output
- □ We will generally ignore this component

## **Power Dissipation Sources**

$$P_{total} = P_{dynamic} + P_{static}$$



### **Dynamic Power Example**

- ☐ 1 billion transistor chip
  - 50M logic transistors
    - Average width: 12  $\lambda$  ( $\lambda$ =25nm)
    - Activity factor = 0.1
  - 950M memory transistors
    - Average width: 4 λ
    - Activity factor = 0.02
  - 1.0 V 65 nm process
  - $-C = 1 fF/\mu m (gate) + 0.8 fF/\mu m (diffusion)$
- □ Estimate dynamic power consumption @ 1 GHz.
   Neglect wire capacitance and short-circuit current.

### Solution

$$C_{\text{logic}} = (50 \times 10^6)(12\lambda)(0.025 \mu m / \lambda)(1.8 fF / \mu m) = 27 \text{ nF}$$

$$C_{\text{mem}} = (950 \times 10^6)(4\lambda)(0.025 \mu m / \lambda)(1.8 fF / \mu m) = 171 \text{ nF}$$

$$P_{\text{dynamic}} = \left[0.1C_{\text{logic}} + 0.02C_{\text{mem}}\right](1.0)^2 (1.0 \text{ GHz}) = 6.1 \text{ W}$$

## **Dynamic Power Reduction**

- $P_{\text{switching}} = \alpha C V_{DD}^{2} f$
- ☐ Try to minimize:
  - Activity factor
  - Capacitance
  - Supply voltage
  - Frequency

## **Activity Factor Estimation**

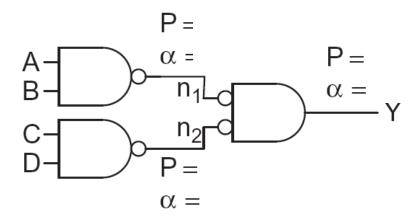
- $\Box \text{ Let } P_i = \text{Prob}(\text{node } i = 1)$ 
  - $-\overline{P}_i = 1-P_i$
- $\Box$   $\alpha_i = \overline{P}_i * P_i$
- $\Box$  Completely random data has P = 0.5 and  $\alpha$  = 0.25
- □ Data is often not completely random
  - e.g. upper bits of 64-bit words representing bank account balances are usually 0
- Data propagating through ANDs and ORs has lower activity factor
  - Depends on design, but typically  $\alpha \approx 0.1$

# **Switching Probability**

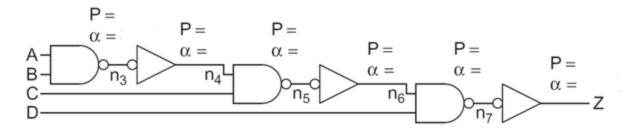
Gate	P <sub>Y</sub>	
AND2	$P_{\mathcal{A}}P_{B}$	
AND3	$P_{\mathcal{A}}P_{B}P_{C}$	
OR2	$1 - \overline{P}_{\mathcal{A}}\overline{P}_{\mathcal{B}}$	
NAND2	$1 - P_A P_B$	
NOR2	$\overline{P}_{\!\mathcal{A}}\overline{P}_{\!\mathcal{B}}$	
XOR2	$P_{\mathcal{A}}\overline{P}_{B} + \overline{P}_{\mathcal{A}}P_{B}$	

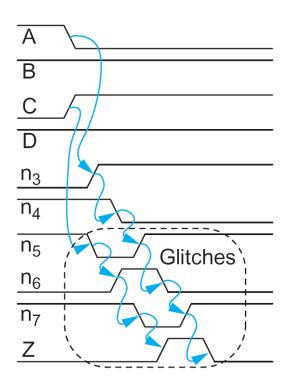
## **Example**

- ☐ A 4-input AND is built out of two levels of gates
- ☐ Estimate the activity factor at each node if the inputs have P = 0.5



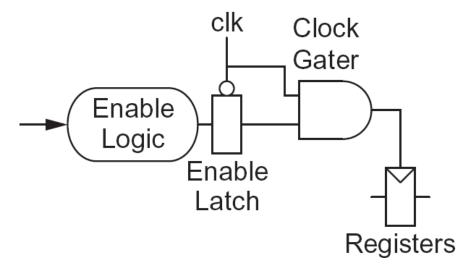
### **Example 2**





## **Clock Gating**

- ☐ The best way to reduce the activity is to turn off the clock to registers in unused blocks
  - Saves clock activity ( $\alpha = 1$ )
  - Eliminates all switching activity in the block
  - Requires determining if block will be used

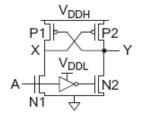


## Capacitance

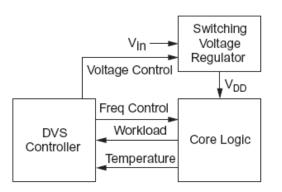
- □ Gate capacitance
  - Fewer stages of logic
  - Small gate sizes
- Wire capacitance
  - Good floorplanning to keep communicating blocks close to each other
  - Drive long wires with inverters or buffers rather than complex gates
    - [stan99] M. Stan, "Optimal Voltages and Sizing for Low Power", Proc. Intl. Conf. VLSI Design, Jan. 1999, pp.428~433.

## Voltage / Frequency

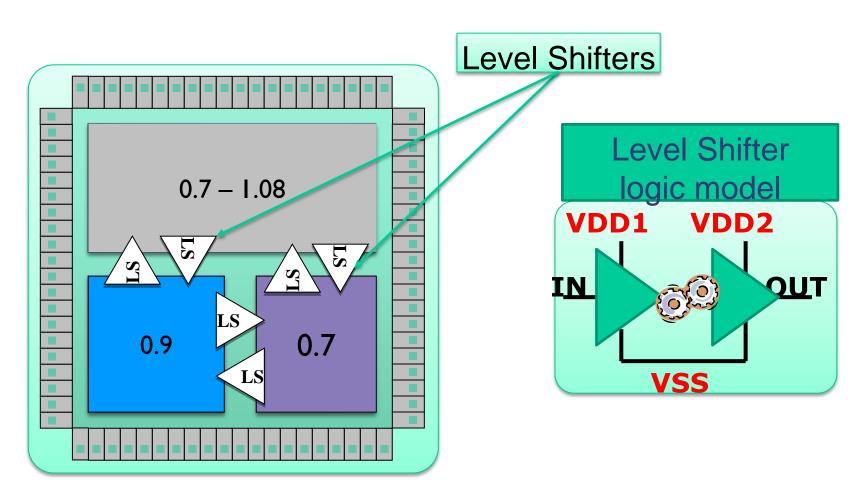
- Run each block at the lowest possible voltage and frequency that meets performance requirements
- Voltage Domains
  - Provide separate supplies to different blocks
  - Level converters required when crossing from low to high  $V_{\text{DD}}$  domains



- Dynamic Voltage Scaling
  - Adjust V<sub>DD</sub> and f according to workload



# Multi-Voltage Design Techniques



### Voltage vs. Delay

- □ How delay will vary if the supply or threshold voltage is changed?
  - Scaling of the RC time constant and of gate delay

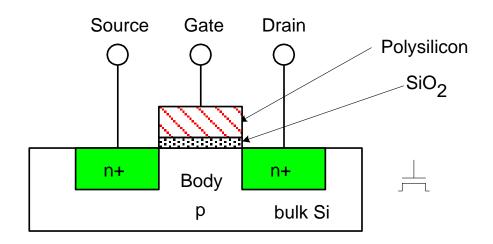
$$\tau = k \frac{CV_{DD}}{\left(V_{DD} - V_{t}\right)^{\alpha}}$$

 As transistors become more velocity saturated, increasing Vgs has less effect on current and α decreases, reaching 1 for transistors that are completely velocity saturated.

$$\tau = k \frac{CV_{DD}}{\left(V_{DD} - V_t^*\right)} = \frac{kC}{1 - \frac{V_t^*}{V_{DD}}}$$

#### **Static Power**

- ☐ Static power is consumed even when chip is quiescent (not switching).
  - Sub-threshold leakage
  - Gate leakage
  - Junction Leakage (negligible)



## Subthreshold Leakage

 $\Box$  For  $V_{ds} > 50 \text{ mV}$ 

$$I_{sub} \approx I_{off} 10^{\frac{V_{gs} + \eta(V_{ds} - V_{DD}) - k_{\gamma}V_{sb}}{S}}$$

 $\Box$   $I_{off}$  = leakage at  $V_{gs}$  = 0,  $V_{ds}$  =  $V_{DD}$ 

Typical values in 65 nm

$$I_{off} = 100 \text{ nA/}\mu\text{m} @ V_t = 0.3 \text{ V}$$

$$I_{off} = 10 \text{ nA/}\mu\text{m}$$
 @  $V_t = 0.4 \text{ V}$ 

$$I_{off} = 1 \text{ nA/}\mu\text{m}$$
 @  $V_t = 0.5 \text{ V}$ 

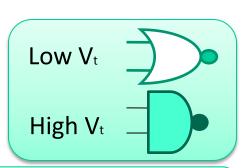
$$\eta = 0.1$$

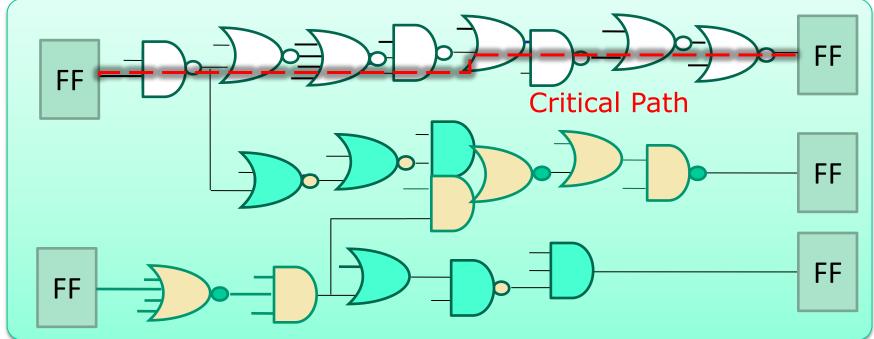
$$k_{v} = 0.1$$

$$S = 100 \text{ mV/decade}$$

### **Multi-Threshold Design Example**

Multi-V<sub>t</sub> libraries enable low leakage design





### **Static Power Example**

- □ Revisit power estimation for 1 billion transistor chip
- Estimate static power consumption
  - Subthreshold leakage
    - Normal  $V_t$ : 100 nA/ $\mu$ m
    - High  $V_t$ : 10 nA/ $\mu$ m
    - High Vt used in all memories and in 95% of logic gates
  - Gate leakage5 nA/μm
  - Junction leakage negligible

### Solution

$$W_{\text{normal-V}_{t}} = (50 \times 10^{6})(12\lambda)(0.025 \mu\text{m}/\lambda)(0.05) = 0.75 \times 10^{6} \mu\text{m}$$

$$W_{\text{high-V}_{t}} = [(50 \times 10^{6})(12\lambda)(0.95) + (950 \times 10^{6})(4\lambda)](0.025 \mu\text{m}/\lambda) = 109.25 \times 10^{6} \mu\text{m}$$

$$I_{sub} = [W_{\text{normal-V}_{t}} \times 100 \text{ nA/}\mu\text{m} + W_{\text{high-V}_{t}} \times 10 \text{ nA/}\mu\text{m}]/2 = 584 \text{ mA}$$

$$I_{gate} = [(W_{\text{normal-V}_{t}} + W_{\text{high-V}_{t}}) \times 5 \text{ nA/}\mu\text{m}]/2 = 275 \text{ mA}$$

$$P_{static} = (584 \text{ mA} + 275 \text{ mA})(1.0 \text{ V}) = 859 \text{ mW}$$

### Stack Effect

- ☐ Series OFF transistors have less leakage
  - $-V_x > 0$ , so N2 has negative  $V_{gs}$

$$I_{sub} = \underbrace{I_{off} 10^{\frac{\eta(V_x - V_{DD})}{S}}}_{N2} = \underbrace{I_{off} 10^{\frac{-V_x + \eta((V_{DD} - V_x) - V_{DD}) - k_y V_x}{S}}}_{N1}$$

$$V_{x} = \frac{\eta V_{DD}}{1 + 2\eta + k_{\gamma}}$$

$$I_{sub} = I_{off} 10^{\frac{-\eta V_{DD}\left(\frac{1 + \eta + k_{\gamma}}{1 + 2\eta + k_{\gamma}}\right)}{S}} \approx I_{off} 10^{\frac{-\eta V_{DD}}{S}}$$

- Leakage through 2-stack reduces ~10x
- Leakage through 3-stack reduces further

## **Leakage Control**

- ☐ Leakage and delay trade off
  - Aim for low leakage in sleep and low delay in active mode
- ☐ To reduce leakage:
  - Increase V<sub>t</sub>: multiple V<sub>t</sub>
    - Use low V<sub>t</sub> only in critical circuits
  - Increase V<sub>s</sub>: stack effect
    - Input vector control in sleep
  - Decrease V<sub>b</sub>
    - Reverse body bias in sleep
    - Or forward body bias in active mode

## **Gate Leakage**

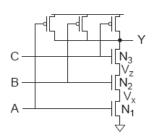
- □ Extremely strong function of t<sub>ox</sub> and V<sub>gs</sub>
  - Negligible for older processes
  - Approaches subthreshold leakage at 65 nm and below in some processes
- An order of magnitude less for pMOS than nMOS
- $\Box$  Control leakage in the process using  $t_{ox} > 10.5 \text{ Å}$ 
  - High-k gate dielectrics help
  - Some processes provide multiple t<sub>ox</sub>
    - e.g. thicker oxide for 3.3 V I/O transistors
- □ Control leakage in circuits by limiting V<sub>DD</sub>

# NAND3 Leakage Example

☐ 100 nm process

$$I_{gn} = 6.3 \text{ nA}$$
  $I_{gp} = 0$ 

$$I_{gn} = 6.3 \text{ nA}$$
  $I_{gp} = 0$   
 $I_{offn} = 5.63 \text{ nA}$   $I_{offp} = 9.3 \text{ nA}$ 



# NAND3 Leakage Example

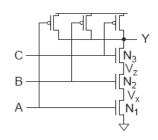
☐ 100 nm process

$$I_{an} = 6.3 \text{ nA}$$

$$I_{qp} = 0$$

$$I_{offn} = 5.63 \text{ nA}$$

$$I_{gn} = 6.3 \text{ nA}$$
  $I_{gp} = 0$   
 $I_{offn} = 5.63 \text{ nA}$   $I_{offp} = 9.3 \text{ nA}$ 



Input State (ABC)	I <sub>sub</sub>	I <sub>gate</sub>	I <sub>total</sub>	V <sub>x</sub>	V <sub>z</sub>
000	0.4	0	0.4	stack effect	stack effect
001	0.7	0	0.7	stack effect	$V_{DD} - V_t$
010	0	1.3	2.0	intermediate	intermediate
011	3.8	0	3.8	$V_{DD} - V_t$	$V_{DD} - V_t$
100	0.7	6.3	7.0	0	stack effect
101	3.8	6.3	10.1	0	$V_{DD} - V_t$
110	5.6	12.6	18.2	0	0
111	28	18.9	46.9	0	0

Data from [Lee03]

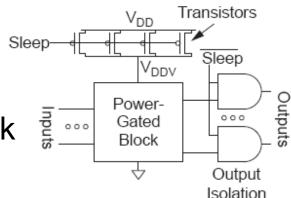
## **Junction Leakage**

- ☐ From reverse-biased p-n junctions
  - Between diffusion and substrate or well
- □ Ordinary diode leakage is negligible
- □ Band-to-band tunneling (BTBT) can be significant
  - Especially in high-V<sub>t</sub> transistors where other leakage is small
  - Worst at  $V_{db} = V_{DD}$
- ☐ Gate-induced drain leakage (GIDL) exacerbates
  - Worst for  $V_{qd} = -V_{DD}$  (or more negative)
  - Pls. refer to Chapter 2.4.3 & Chapter 5.3 of Reference 3 for more details.

## **Power Gating**

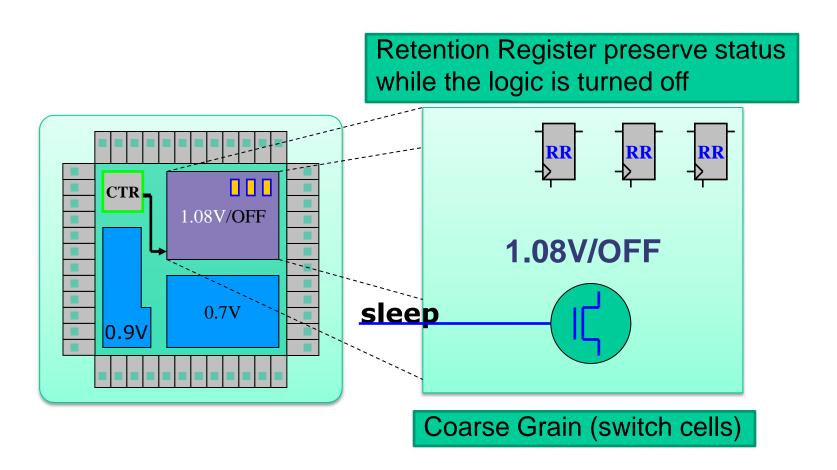
- ☐ Turn OFF power to blocks when they are idle to save leakage

  Header Switch Transistors
  - Use virtual  $V_{DD}$  ( $V_{DDV}$ )
  - Gate outputs to prevent invalid logic levels to next block

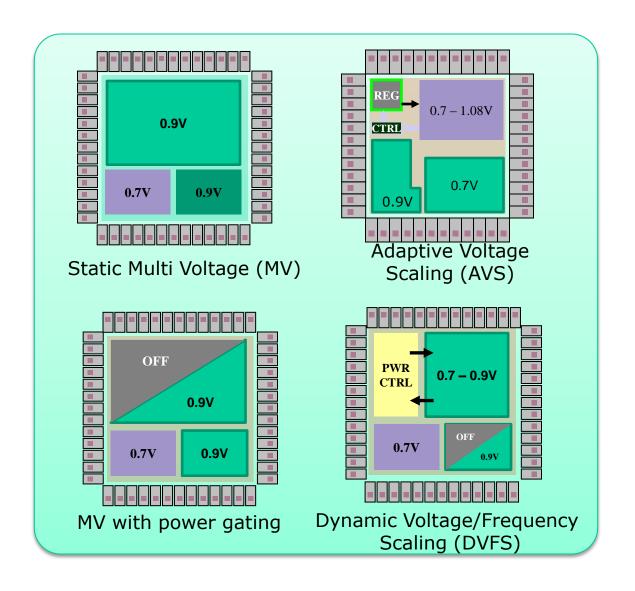


- □ Voltage drop across sleep transistor degrades performance during normal operation
  - Size the transistor wide enough to minimize impact
- ☐ Switching wide sleep transistor costs dynamic power
  - Only justified when circuit sleeps long enough

# Power Gating: retention register



### **Low Power Design Techniques**



### Reference

☐ Reference 3. Chapter 5